

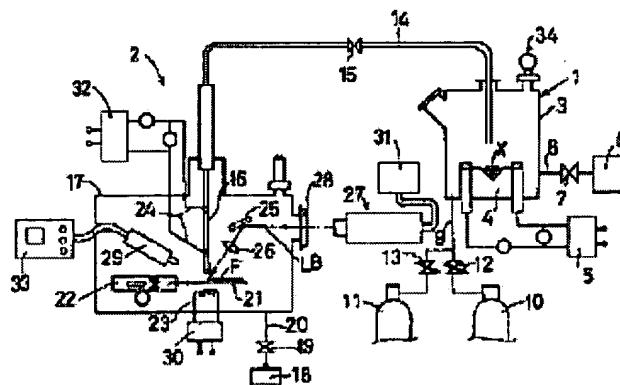
METHOD AND DEVICE FOR FORMING SUPERFINE-PARTICLE FILM BY GAS DEPOSITION

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Inventor: HAYASHI CHIKARA; others: 01
Applicant: VACUUM METALLURGICAL CO LTD
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Abstract of JP6049656

PURPOSE: To extremely easily provide a partial characteristic to the deposited film of superfine particles on a substrate, to easily form a minute capacitor and to repair a high-temp. superconducting film by utilizing a superfine-particle film formed by gas deposition.

CONSTITUTION: A carrier gas and the superfine particles having $\leq 1\text{ }\mu\text{m}$ size are simultaneously transported on a substrate 21 to form a superfine-particle film. In this case, the heating by a nozzle and the heating of the superfine-particle film surface when the superfine particles are deposited are separately or simultaneously carried out to form the film. A heater 24 is arranged at the tip of a nozzle 16 for ejecting the superfine particles and carrier gas on the substrate 21 to heat the nozzle 16, and a laser-beam heater 27 is set close to the nozzle tip to heat the superfine particles to be deposited on the substrate to constitute the superfine-particle film forming device.



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